Supporting Infromation for:

Direct electroplating of Ag nanowires using superionic conductors

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^a State Key Lab of New Ceramics and Fine Processing, School of Materials Science and Engineering, Tsinghua University, Beijing 100084, China * Correspondence: huiwu@tsinghua.edu.cn We have recorded the I-t curve of the electroplating process (Fig. S1), and the electrodeposited layer is characterized in detail. Optical (Fig. S2) and SEM pictures (Fig. S4 and Fig. S5), XRD (Fig. S3) and EDS (Fig. S6) results are presented to show the composition, and detailed morphology of the plated layer, which is made of uniformed nanowire arrays.



Figure S1. Current-time curve of all-solid electrodeposition Ag. The all-solid electrodeposition process consists two consecutive sessions. During the 0-10000s plating session, the voltage is set at -0.05V for Ag to deposit on the substrate. During the 10000-11000s plating session, the voltage is set at 0.05V for the interfaced Ag to slightly dissolve.



Figure S2 Photos of all-solid electrodeposited Ag and Cu layers. a) The "to the electrode side" of Ag layer; b) The "to the electrolyte side" of Ag layer; c) The "to the electrolyte side" of Cu layer; d) The "to the electrolyte side" of Cu layer.



Figure S3 XRD results of all-solid electrodeposited Ag and Cu layers. a) All-solid electrodeposited Ag layer. b) All-solid electrodeposited Cu layer.



Figure S4. EDS results of Ag nanowire arrays. The layer is made of pure Ag. Scale bar, 1 μ m (a).



Figure S5 SEM pictures showing the surface morphology of all-solid electrodeposited Ag and Cu layers. a) and b) Surface of all-solid electrodeposited Ag layer. c) and d) Surface of all-solid electrodeposited Cu layer. Scale bar, 5 μ m (a and c), 1 μ m (b and d).



Figure S6 Supplementary SEM pictures of Ag nanowire arrays. a) Freshly grown Ag nanowires at deposition charge density of 2 C/cm²; b) Ag nanowires at deposition charge density of 10 C/cm². Scale bar, 10 μ m (a), 5 μ m (b).



Figure S7. TEM pictures of nanowire margins on different sections (a-d) of a single silver nanowire. Scale bar,10nm.



Figure S8. XRD results of the electrolyte before and after all-solid Ag electroplating. The diffraction peaks fits well with standard RbAg₄I₅ XRD pattern (ICSD #27203), which indicates that the electrolyte shows no phase transition during electroplating process.



Figure S9. SEM image showing surface morphology deatails of $RbAg_4I_5$ after electroplating. Surface roughness ~100 nm, scale bar, 500 nm.



Figure S10. SEM images showing dispersed $RbAg_4I_5$ samples in resin. Scale bar, 1 µm (a), 500 µm (b).